

**SPECIFICATION AMENDMENT**

Please amend the paragraph beginning on page 1, line 1 as follows:

“The invention relates to a method of manufacturing a filter for retaining a substance originating from a radiation source[[as defined in the opening part of claim 1]] wherein the filter is transparent to extreme ultraviolet and/or soft X-ray radiation, and to a device [[as defined in the opening part of claim 12]] having a filter for retaining a substance originating from a radiation source wherein the filter is transparent to extreme ultraviolet and/or soft X-ray radiation. The invention also relates to the use of a device according to the invention in EUV lithography.”